



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

#3/Amendment  
a total  
5/1/02

**In re Application of**

**PEI-REN JENG.**

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**: Group Art Unit: 2823**

**Serial No.: 09/729,833**

**: Examiner: Lynette Hsien-Ming Lee**

**Filed: DEC, 1, 2000**

**For: METHOD FOR PATTERNING A DUAL DAMASCENE**

**AMENDMENT AND RESPONSE**

Honorable Commissioner for Patents  
Washington, D.C. 20231

RECEIVED  
APR 30 2002  
TECHNOLOGY CENTER 2800

Sir:

This paper is in response to the Official Action dated January 29, 2002. In that Official Action, Claims 1-50 are rejected under 35 U.S.C. 112, second paragraph, and 35 U.S.C. 103(a); and further, Claims 10, 14, 17, 24, 27 and 29 are objected. Kindly amend and reconsider the application in accordance with the following particulars:

**IN THE CLAIMS:**

Claims 1 through 50 have been deleted.

Please add new claims 51 - 63 as follows:

51. A method for forming a dual damascene opening, comprising:  
providing a substrate with a dielectric layer in a certain thickness thereon;

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